

**ALIGNMENT SYSTEM AND METHOD USING BRIGHT SPOT  
AND BOX STRUCTURE**

**ABSTRACT OF THE DISCLOSURE**

5           There is provided a method for aligning a  
semiconductor wafer and a mask. A semiconductor wafer is  
provided having an alignment mark formed thereon. A mask  
is provided having a pattern formed thereon. The mask is  
illuminated so as to create a bright spot thereon by a  $0-\pi$   
10   phase conflict. The alignment mark is aligned with the  
bright spot, so as to align the semiconductor wafer with  
the mask. Preferably, the method includes the step of  
creating the alignment mark on the semiconductor wafer in a  
form of a frame. Moreover, preferably, the creating step  
15   includes the step of creating the frame to minimize an  
impact of film stack variations.